



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:

KOZAWA et al.

Attorney Docket No: 100021-00065

Application No. 10/005,347

Art Unit: 1712

Filed: December 7, 2001

Examiner: K. Peng

For: SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,
RESIST COPOSITION EMPLOYING IT, PATTERN-FORMING METHOD AND
ELECTRONIC DEVICE FABRICATION METHOD

AMENDMENT UNDER 37 C.F.R. § 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

April 9, 2004

Sir:

In reply to the Office Action dated December 9, 2003, the period for response being extended to April 9, 2004 by the attached Petition for Extension of Time, Applicants respectfully request reconsideration of the above-identified application in view of the following amendments and remarks: